

Real-time control of track etching and recent experiments relevant to micro and nano fabrication

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Part (1) of the report sketches a computer controlled electrolytic cell system for track etching and electro replication. Track and bulk etch rates are determined in real-time. Processing can be stopped at a prescribed parameter, e.g. current, diameter, or charge. The system can be used to rapidly screen prospective track sensitive materials, selective etchants, and electro replication processes, and can thus reduce the number of necessary SEM observations. Part (2) of the report describes recent experiments relevant to micro and nano fabrication.